

Notice of References Cited	Application/Control No. 10/678,003	Applicant(s)/Patent Under Reexamination PADHI ET AL.	
	Examiner Edna Wong	Art Unit 1753	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-3,934,985	01-1976	Kitaev et al.	428/598
*	B	US-2007/0014075	01-2007	Ritter et al.	361/306.3
*	C	US-6,174,812	01-2001	Hsiung et al.	438/687
*	D	US-6,319,387	11-2001	Krishnamoorthy et al.	205/240
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	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Moiseeva et al., "Palladium-Copper Alloy Electrodeposition with a Pulsed Current", Intensifik. Tekhnol. Protsessov pri Gsazhdenil Met. I Splavov (no month, 1997), pp. 92-93, From: Ref. Zh. Metall, 1978, Abstr. No. 2G293. Abstract only.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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